

SHEET 1 of 2

<b>INFORMATION DISCLOSURE CITATION</b>  <b>PTO-1449</b>	<b>Atty. Docket No.</b>	<b>Serial No.</b>
	NTI-029	10/005.615
	<b>Applicant</b>	
	CHANG, Fang-Cheng	
	<b>Filing Date</b>	<b>Group</b>
	11/7/2001	2825

**U.S. PATENT DOCUMENTS**

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
W	6,014,456	1/11/2000	Tsudaka	382	144	7/15/1996
	6,154,563	11/28/2000	Tsudaka	382	144	12/17/1998
	6,298,473 B1	10/2/2001	Ono, et al.	716	21	12/3/1998
	6,338,922 B1	1/15/2002	Liebmann, et al.	430	5	5/8/2000
	6,453,457 B1	9/17/2002	Pierrat, et al.	716	19	9/29/2000
	2002/0100004 A1	7/25/2002	Pierrat, et al.	716	5	3/15/2002

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SHEET 2 of 2

<b>INFORMATION DISCLOSURE CITATION</b>  <b>PTO-1449</b>		<b>Atty. Docket No.</b> NTI-029  <b>Applicant</b> CHANG, Fang-Cheng  <b>Filing Date</b> 11/7/2001	<b>Serial No.</b> 10/005,615  <b>Group</b> 2825
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>			
<b>EXAMINER'S INITIALS</b>	<b>CITATION</b>		
<i>W</i>	Kirk, J., "Measurement of Astigmatism in Microlithography Lenses", IBM Microelectronics (7 pages).		
	Cobb, N., et al., "Fast, Low-Complexity Mask Design", SPIE, Vol. 2440, pp. 313-327, February 22-24, 1995.		
	Flagello, D., et al., "Towards a Comprehensive Control of Full-Field Image Quality in Optical Photolithography", SPIE, pp. 1-14, March 1997.		
	Cobb, N., et al., "Experimental Results on Optical Proximity Correction With Variable Threshold Resist Model", SPIE, Vol. 3051, pp. 458-468, March 12-14, 1997.		
	Cobb, N., "Fast Optical and Process Proximity Correction Algorithms for Integrated Circuit Manufacturing", Dissertation, University of California at Berkeley. UMI Microform 9902038 (139 pages).		
	Toublan, O., et al., "Phase Aware Proximity Correction for Advanced Masks", SPIE, Vol. 4000, pp. 160-170, March 1-3, 2000.		
	Anonymous, "Parameterization For Full Shape And Rule Dependent Dissection", IPCOM000009587D, September 4, 2002 (9 pages).		

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